

FORM PTO 1449 (modified) U. S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)			ATTY DOCKET NO. 03500.014730.1	APPLICATION NO. 10/609,421		
			APPLICANT HIROSHI OHKURA ET AL.			
			FILING DATE July 1, 2003	GROUP 1756		
U. S. PATENT DOCUMENTS						
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS
FOREIGN PATENT DOCUMENTS						
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS
<i>Kay</i>	JP	2000-195036	07/14/00	Japan		
"	JP	10-121292	05/12/98	Japan		
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)						
<i>Kay</i>		Hideki Masuda et al., "Fabrication of Gold Nanodot Array Using Anodic Porous Alumina as an Evaporation Mask," 35 <u>Jpn. J. Appl. Phys.</u> L126-L129 (1996).				
"		O. Jessensky et al., "Self-Organized Formation of Hexagonal Pore Arrays in Anodic Alumina," 72(10) <u>Appl. Phys. Lett.</u> 1173-1175 (March 1998).				
EXAMINER	<i>Teru Noda</i>		DATE CONSIDERED		<i>3/17/04</i>	

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Sheet 1 of 1

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			APPLICANT HIROSHI OHKURA ET AL.				
			FILING DATE Herewith	GROUP N.Y.A.			
U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>Nyb</i>		5,882,823	03/16/99	Neary	430	5	
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER	<i>Kenn M. Burtis</i>		DATE CONSIDERED	3/17/04			

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Sheet 2 of 2

FORM PTO 1449 (modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)			ATTY DOCKET NO. 03500.014730.1		APPLICATION NO. Div. of 09/649,598		
			APPLICANT HIROSHI OHKURA ET AL.				
			FILING DATE Herewith		GROUP N.Y.A.		
U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>Y</i>		6,139,713	10/31/00	Masuda et al.	205	206	
<i>Y</i>		6,278,231 B1	08/21/01	Iwasaki et al.	313	310	
<i>Y</i>		2002/0014621 A1	02/07/02	Den et al.	257	3	
<i>Y</i>		2002/0034662 A1	03/21/02	Den	428	692	
<i>Y</i>		6,476,409 B2	11/05/02	Iwasaki et al.	257	13	
<i>Y</i>		6,464,853 B1	10/15/02	Iwasaki et al.	205	118	
<i>Y</i>		6,214,738 B1	04/10/01	Aiba et al.	438	707	
<i>Y</i>		4,086,694	05/02/78	U	438	361	
<i>Y</i>		4,923,301	05/08/90	White	356	356	
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT
<i>Y</i>	JP	7-171984	07/11/95	Japan			Translation
<i>Y</i>	JP	11-200090	07/27/99	Japan			Abstract
<i>Y</i>	EP	0 931 859	07/28/99	Europe			
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)							
<i>Y</i>	Hutley, M.C. "Coherent Photofabrication", Opt. Eng., Vol. 15, No. 3 (1976), pp. 190-196.						
<i>Y</i>	Decker, et al. "Generating...Reversal," J. Vac. Sci. Technol. B15(6), Nov. 1997 pp. 1949-1953.						
<i>Y</i>	Furneaux, et al. "The formation...aluminum", Nature, Vol. 337, P.147-149 (1989).						
<i>Y</i>	Masuda, "Anodically High Level"; Solid State Phys. , Vol. 3, No. 5, pp. 493-499 (1996).						
EXAMINER	<i>Y</i>		DATE CONSIDERED		<i>3/17/04</i>		

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